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ABSTRACT OF THE DISCLOSURE

This invention relates to an illumination system for scanning lithography with wavelengths  $\leq 193$  nm, particularly EUV lithography, for the illumination of a slit. The illumination system includes a light source, and a field lens group. The field lens group is shaped so that an illuminated field is distorted in a plane of a reticle perpendicular to a scanning direction.

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